

**3rd International Workshop on Superconducting Sensor and Detectors
IWSSD 2016 14-17 Nov. 2016 TUKUBA**

Phase slips and Superconductor- Insulator transition in Nitride nanowire

Kazumasa Makise

**Advanced ICT Research Institute, National
Institute of Information and Communications
Technology (NICT)**

Scientific Reports 6, (2016) 27001

Scientific Reports 4, (2014) 5740



Outline



Background and Motivation

Phase slips (Quantum and Thermal Activation)

Superconductor-Insulator transition(SIT)

Duality analysis

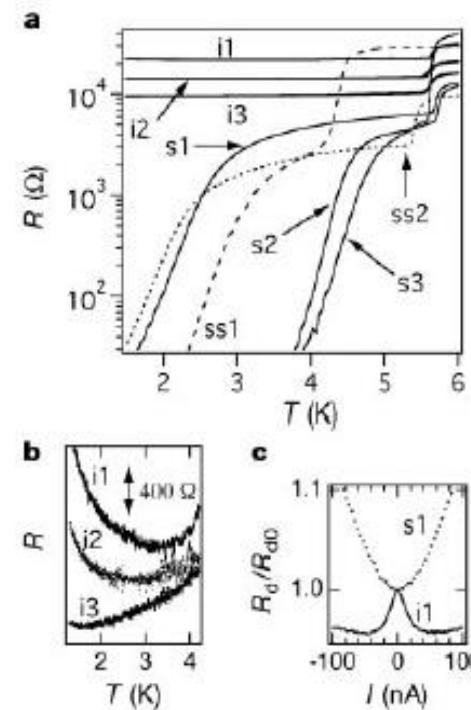
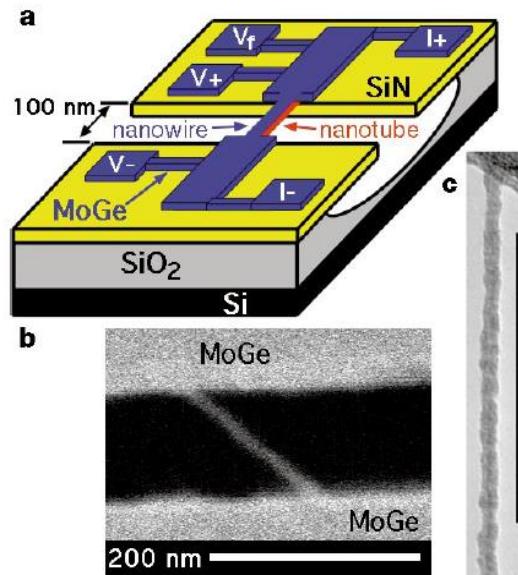
Future work and summary



Background



Quantum suppression of superconductivity (quantum phase slips)



A. Bezryadin, Lau, Tinkham
Nature 404 971 (2000)

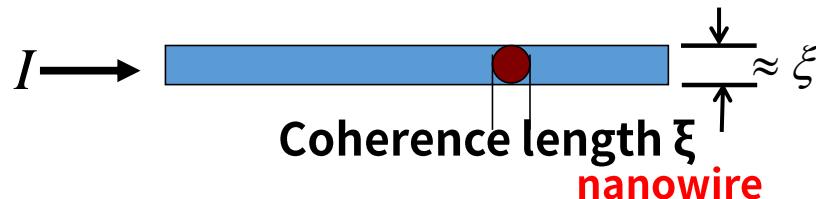


Phase slips



$T < T_c$

Normal conducting core due to fluctuations

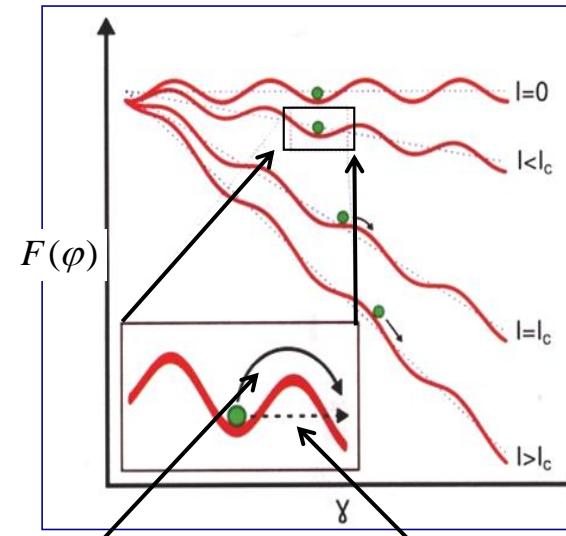


Potential barrier ΔF for Cooper pairs

Phase ϕ shifts occurs passing over
 ΔF

$$V = \left(\frac{\hbar}{2e}\right) \frac{d\phi}{dt}; \quad \text{Josephson equation}$$

$$R(T = 0) \neq 0$$



Thermal Activation
→TA Phase Slip
TAPS

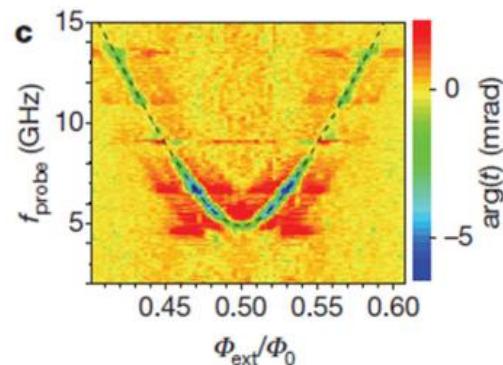
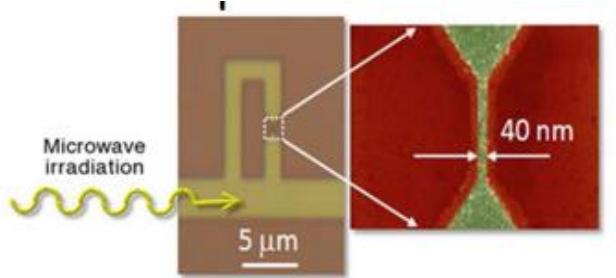
Quantum Tunneling
→Q Phase Slip
QPS



Coherent Quantum Phase slips

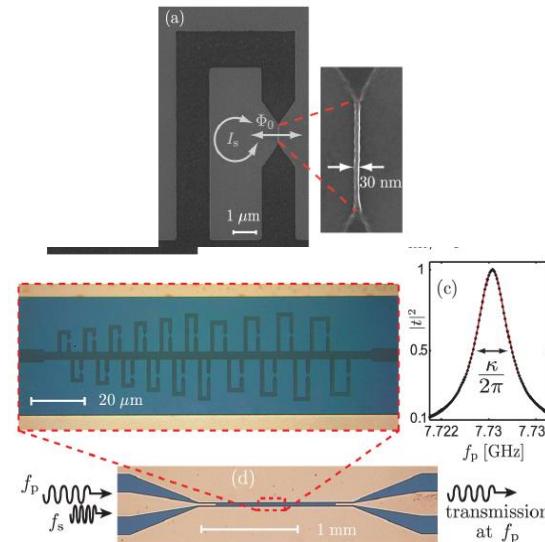


InOx nanowire



Astafiev et al.
Nature 484 355-358 (2012)

NbN nanowire



Peltonen et al.
Phys. Rev. B (2013)

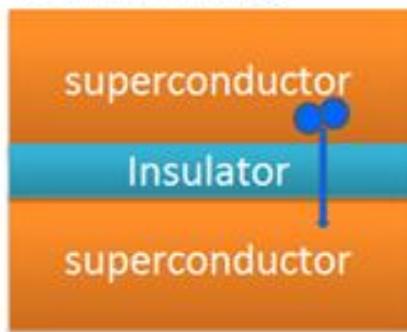


Duality



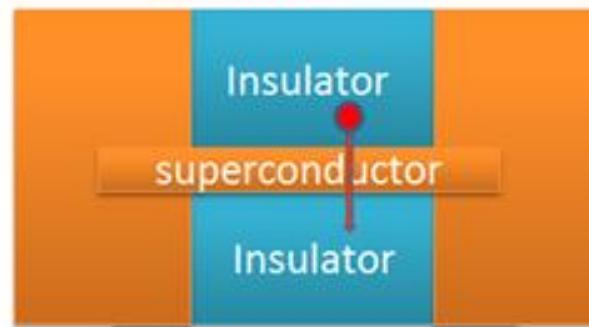
Josephson Junction

Cooper pair tunneling



QPS Junction

Phase tunneling



$$H_{JJ} = E_C(n - n_c)^2 - \left(\frac{E_J}{2} \sum_n |n+1\rangle\langle n| + h.c \right)$$

$$H_{QPS} = E_L(n - f)^2 - \left(\frac{E_S}{2} \sum_n |n+1\rangle\langle n| + h.c \right)$$

Josephson junction
Charging energy E_C
Josephson energy: E_J
Phase : Φ
Voltage : V

QPS nanowire
Inductance energy E_L
QPS energy: E_S
Charge : 2 e
Current : I

Some devices(ex. Qubits) without Josephson junction

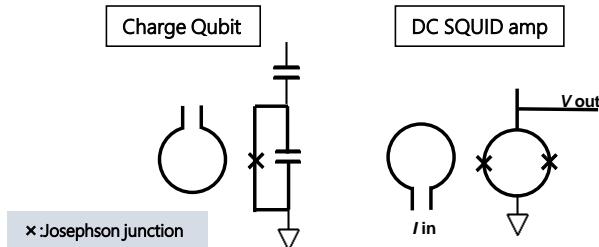


National Institute of Information and Communications Technology

Duality devices

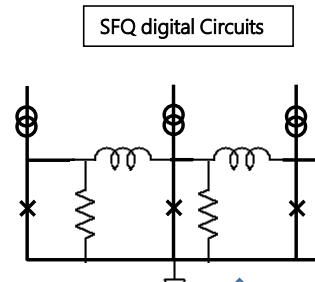


Josephson junction devices



Josephson Voltage standard

$$V = N \times \Phi \times f$$



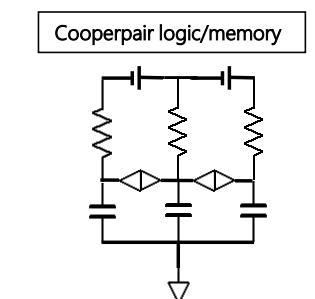
SFQ digital Circuits



Duality

QPS Current Standard

$$I = N \times 2 \times e \times f$$



Cooperpair logic/memory

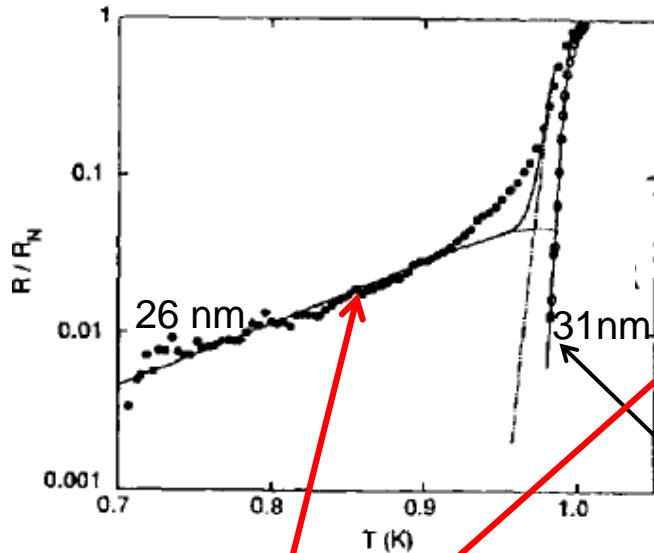
QPS devices



Phase Slip (R-T)



Pb/In



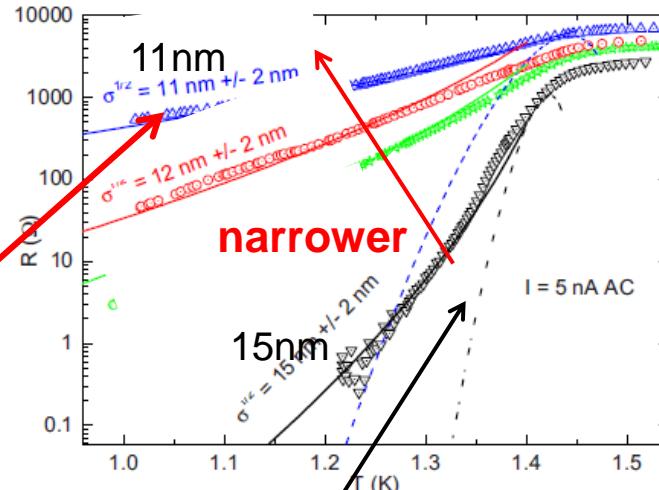
Physica B 203 (1994) 460-466
N. Giordano

Quantum phase slip(QPS)
▪ Schon and Zaikin(1990)



Al

PHYSICAL REVIEW B 77, 054508 (2008)
ZGIRSKI *et al.*



Thermal Activated phase slip(TAPS)
▪ Langer, Ambegaokar (1967)
▪ McCumber, Halperin(1970)

TA model & MQT model



J. S. Langer and V. Ambegaokar, Phys. Rev. **164**, 498 (1967); D. E. McCumber and B. I. Halperin, Phys. Rev. B **1**, 1054 (1970). **LAMH theory**

- thermal activation ;

$$R_{\text{TA}} = \frac{\phi_0 \Omega}{k_B T / \phi_0} \exp[-\Delta F / k_B T]$$

magnetic barrier

$$\Delta F = \sqrt{2} \sigma H_c^2 \xi / 3\pi$$

associated attempt frequency

$$\Omega = \frac{L}{2\pi^2 \xi \tau_{\text{GL}}} \left[\frac{3\pi \Delta F}{k_B T} \right]^{1/2}$$

GL relaxation time

$$\tau_{\text{GL}} = \frac{\pi \hbar}{8k_B(T_c - T)}$$

change of energy scale $k_B T$ to \hbar / τ_{GL}

N. Giordano, Physica (Amsterdam) **203B**, 460 (1994)

D. S. Golubev and A. D. Zaikin, Phys. Rev. B **64**, 014504 (2001).

$$\begin{aligned} R_{\text{MQT}} &= \left(\frac{\hbar}{4e^2} \right) \left(\frac{\hbar \Omega}{\hbar / \alpha \tau_{\text{GL}}} \right) \exp \left(-\frac{\Delta F}{\hbar / \alpha \tau_{\text{GL}}} \right) \\ &= \alpha R_Q \left(\frac{8\sqrt{3}L}{2\pi^{5/2}\xi_0} \right) 0.83 \left(\frac{LR_Q}{\xi_0 R_N} \right)^{1/2} \left[\left(1 - \frac{T}{T_c} \right)^{7/4} \frac{T_c}{T} \right] \exp \left[-0.83 \left(\frac{LR_Q}{\xi_0 R_N} \right) \left[\left(1 - \frac{T}{T_c} \right)^{1/2} \right] \right] \end{aligned}$$



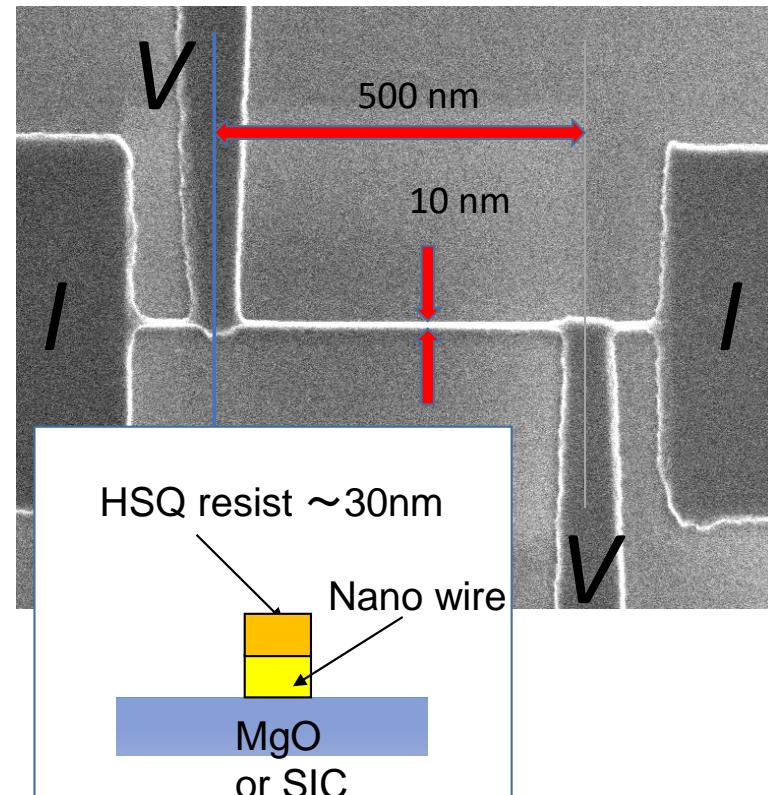
,where $R_Q = h/4e^2$

National Institute of Information and Communications Technology

Experimental details



- Niobium Nitride (NbN), Niobium Titanium Nitride(NbTiN),
Titanium Nitride(TiN)
Molybdenum Nitride (MoN)
MgO (100) substrate
3C-SiC/Si (100) substrate
- DC reactive magnetron sputtering method
- Reactive Ion Etching
- $d=2\text{-}10\text{ nm}$, $L = 250\text{-}1000\text{nm}$
- $w = 10\text{-}300\text{nm}$
- $R(T)$, $R(H)$, I-V measurement



Nitride nanowire (NbN)



Epitaxial NbNnanowire

	Lattice Type	Lattice Constants (nm)
MgO	NaCl-cubic	0.439
3C-SiC	NaCl-cubic	0.421
NbN	NaCl-cubic	0.436
NbTiN	NaCl-cubic	0.440

Lattice mismatch

$$\nu_{NbN-MgO} = \frac{a_{MgO} - a_{NbN}}{a_{NbN}}$$

1 %

$$\textcolor{red}{\nu_{NbN-SiC} = \frac{a_{SiC} - a_N}{a_N}}$$

=-0.7 %

Lattice mismatch between NbN and 3C-SiC/Si is smaller.

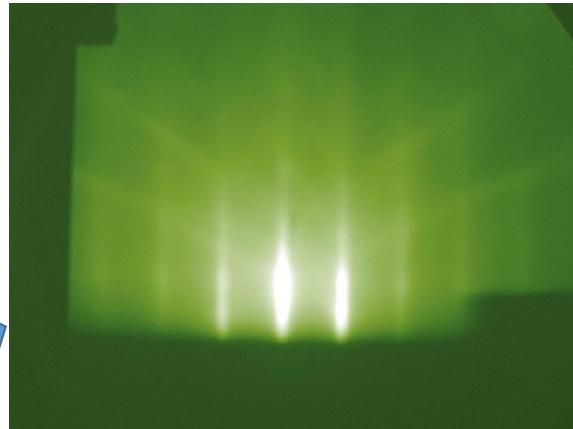


Sample preparation

$\text{H}_2\text{SO}_4 + \text{H}_2\text{O}_2$ 85 °C 10 min Remove organic contamination



Dipped into a buffered HF solution
Remove any native oxide.



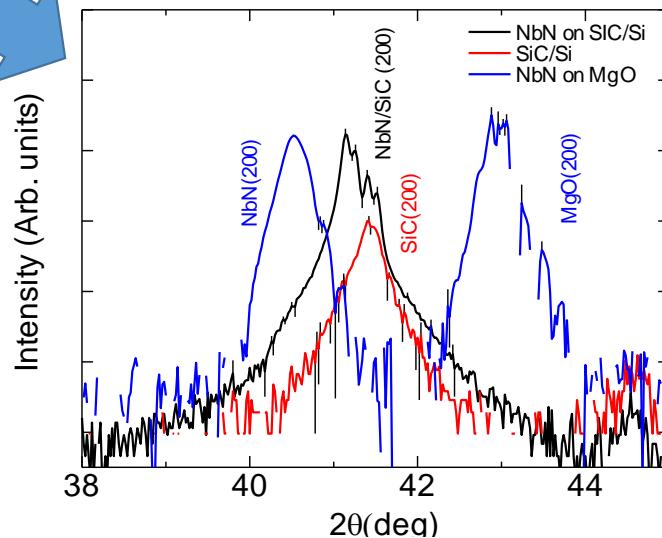
NbN thin film deposition



EB lithography



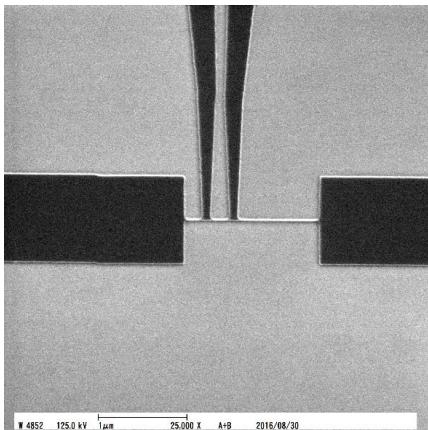
Etching (DRY:RIE)



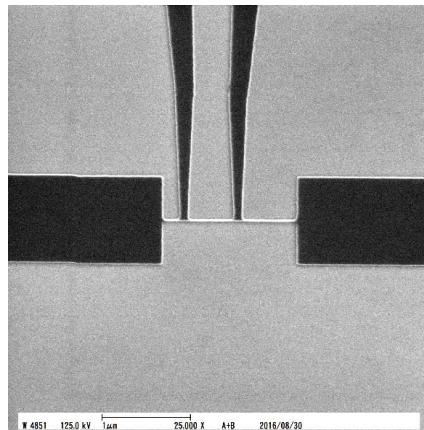
Nitride nanowire (NbN)



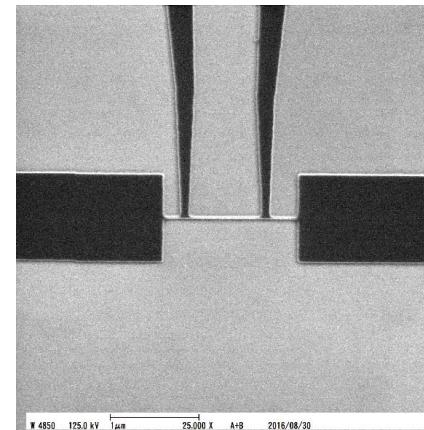
Using four-probe method to eliminate the contact resistance.



$L = 300 \text{ nm}$

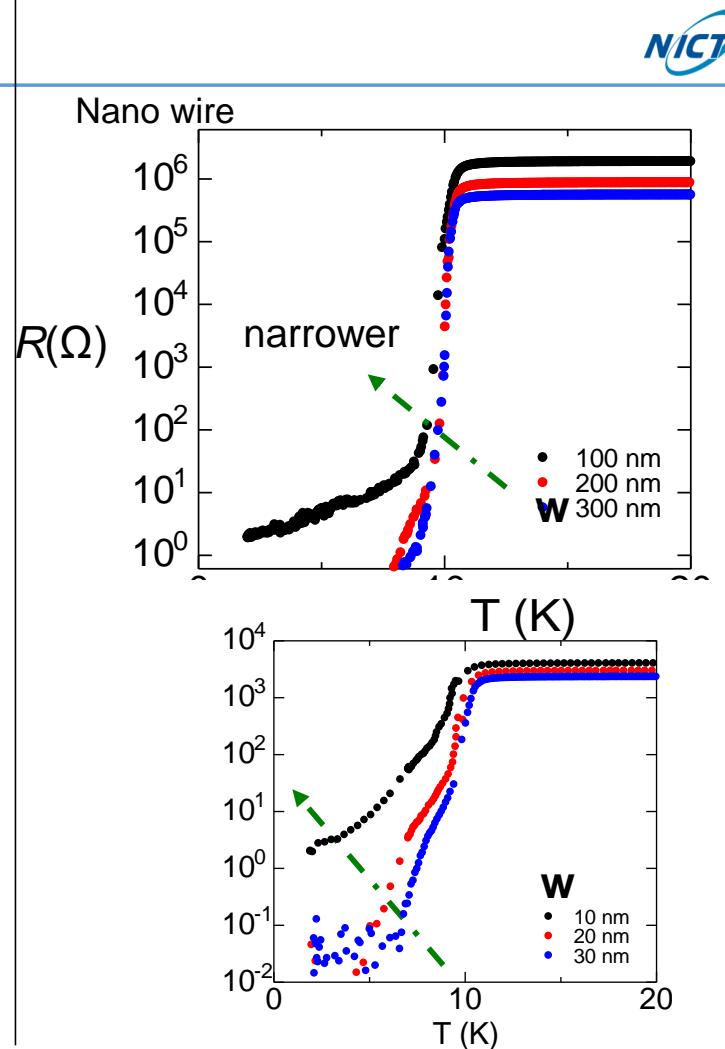
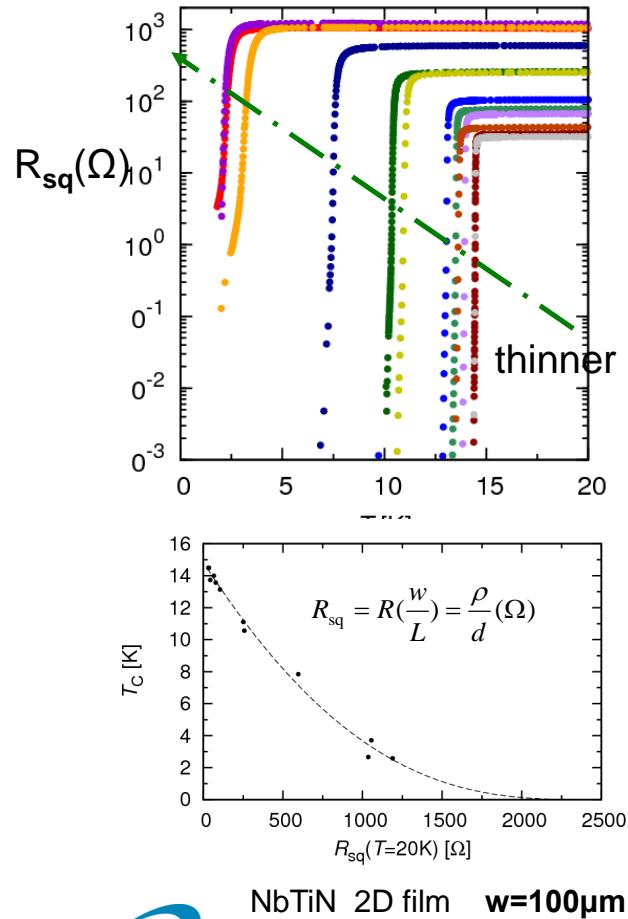


$L = 600 \text{ nm}$

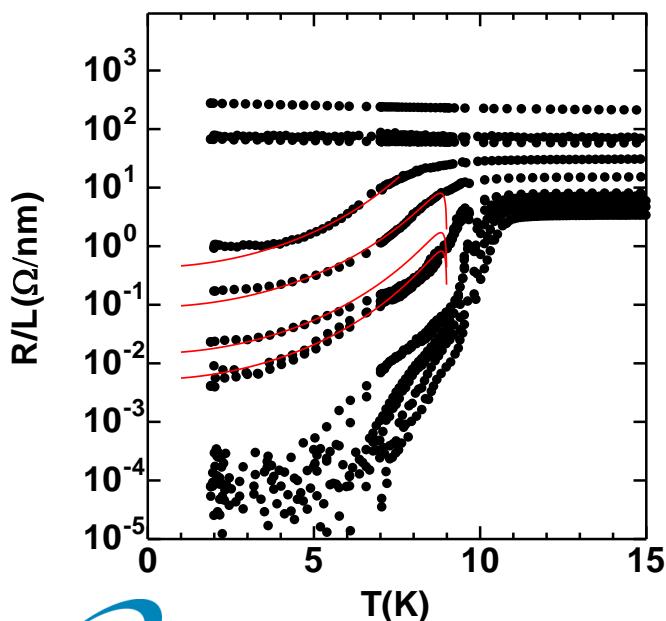


$L = 900 \text{ nm}$

Size dependence



QPS fitting

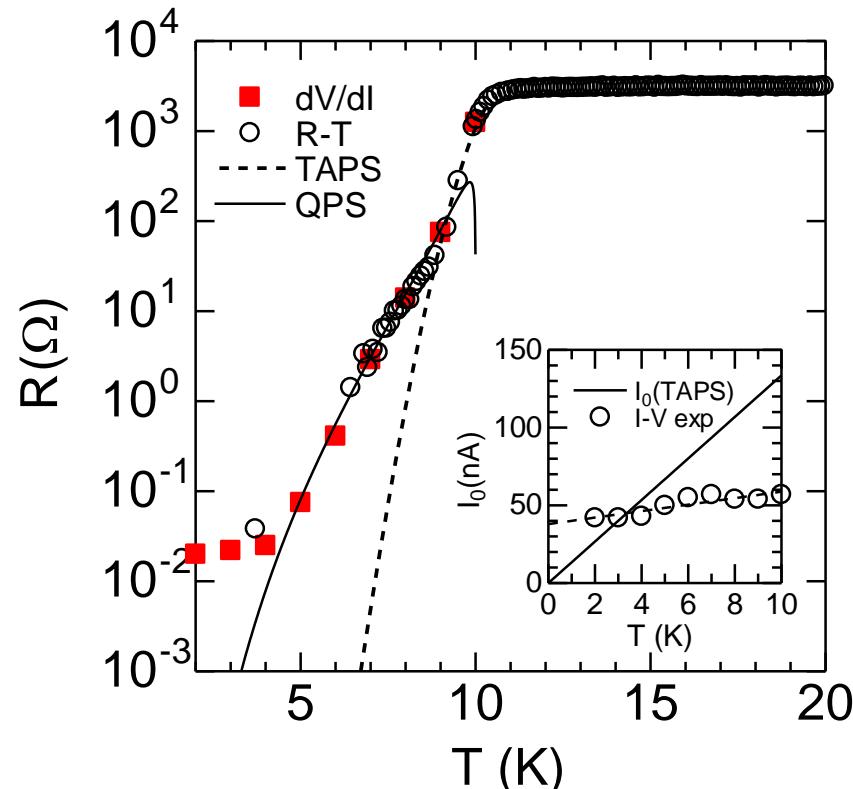
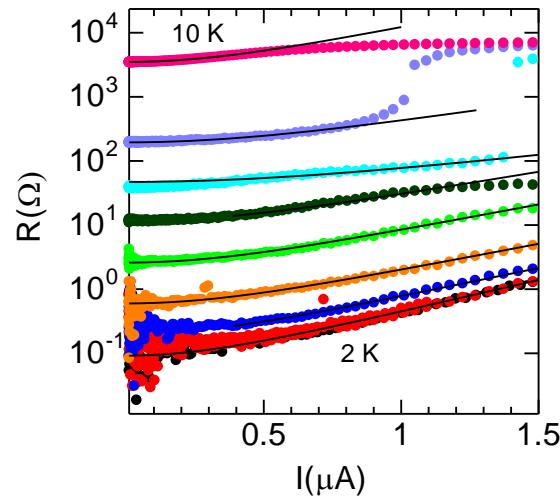


$$\begin{aligned}
 R_{\text{QPS}}(T) &= \left(\frac{h}{4e^2}\right) \left(\frac{\hbar\Omega}{\hbar/\alpha\tau_{GL}}\right) \exp\left(-\frac{\Delta F}{\hbar/\alpha\tau_{GL}}\right) \\
 R_{\text{QPS}}(T) &= \alpha R_Q \left(\frac{8\sqrt{3}L}{2\pi^{5/2}\xi_0}\right) 0.83 \left(\frac{LR_Q}{\xi_0 R_N}\right)^{1/2} \left[\left(1 - \frac{T}{T_C}\right)^{7/4} \frac{T_C}{T}\right] \\
 &\quad \exp\left[-0.83 \left(\frac{LR_Q}{\xi_0 R_N}\right) \left[\left(1 - \frac{T}{T_C}\right)^{1/2}\right]\right] \\
 I_{\text{QPS}} &= \left(\frac{2e}{\beta\pi\tau_{GL}}\right) \\
 V_{\text{QPS}} &= I_{\text{QPS}} R_{\text{QPS}} \sinh\left(\frac{I}{I_{\text{QPS}}}\right)
 \end{aligned}$$

Zaikin et al., Phys. Rev. Lett. 78, 1552 (1997); D. S. Golubev and A. D. Zaikin, Phys. Rev. B 64, 014504(2001).

National Institute of Information and Communications Technology

TAPS fitting (I-V & R-T Curve)



$$dV/dI = R_{\text{TAPS}}(T) \cosh(I/I_0)$$

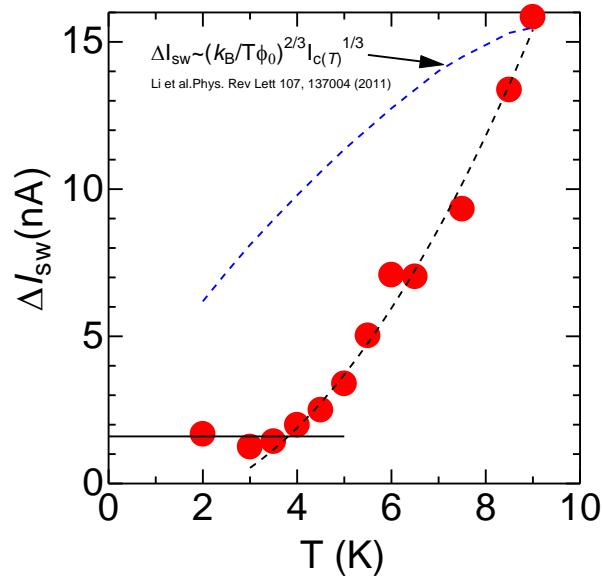
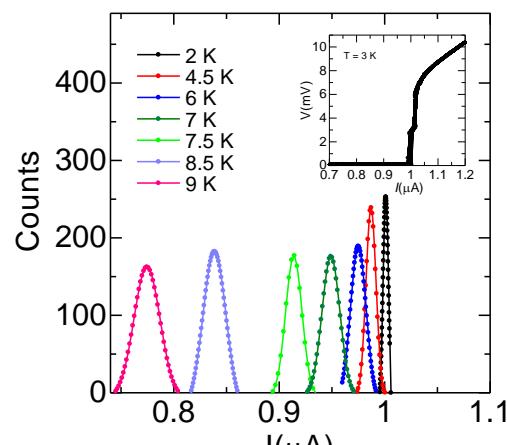
$$I_0(T) = 4ekT/h \quad (\text{By TAPS, } I_0 \text{ depend on only Temperature.})$$





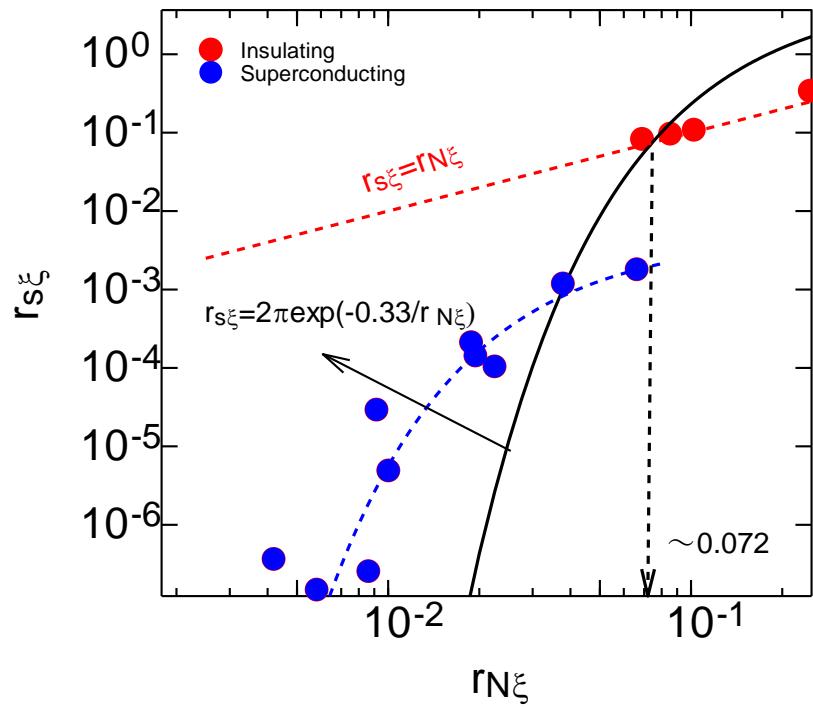
Switching Current

I_{sw} distribution at different temperature





Estimation of Cross over for SIT based on QPS model



superconducting state resistance R_s
 measured in units of R_Q for length in
 units of ξ

$$(R_{QPS} = R_s)$$

$$\begin{aligned} (R_s / R_Q)(\xi / L) &\equiv r_{S\xi} \\ &= 2\pi \exp[-0.33(R_Q / R^N)(L / \xi)] \\ &= 2\pi \exp[-0.33 / r_{N\xi}] \end{aligned} \quad (1)$$

$$\text{at cross over, } r_{S\xi} = r_{N\xi} \quad (2)$$

$$\Rightarrow r_{N\xi} = 1/13.3 \approx 0.072$$

$$(R^N / L)_{c.o} = R_Q / 13.3\xi \approx 485\Omega / \xi(0)$$

$\xi(0) \approx 9\text{nm}$ for presents pecimens

$$(R^N / L)_{c.o} \approx 54\Omega / \text{nm}$$



PS & Inductance energy : E_s , E_L

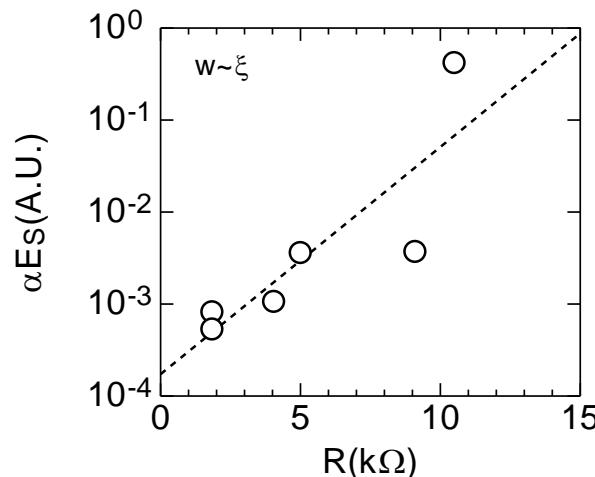
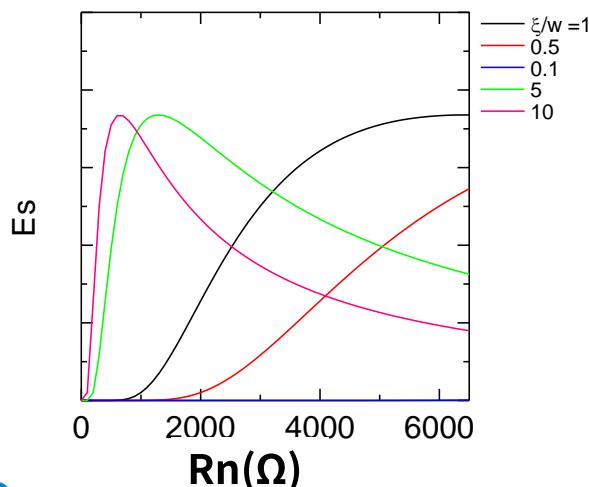


According to the theory Quantum phase slip is dependent on sheet resistance.

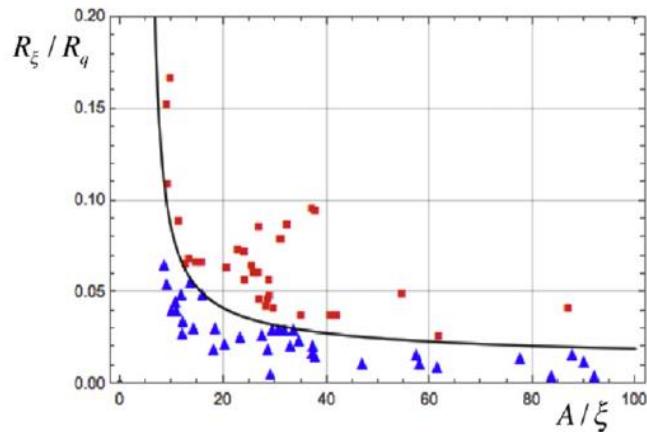
But it remains unclear whether the characteristics of the QPS depend on disorder

$$E_S = a \frac{A}{\xi} k_B T_C \frac{R_Q}{R_\xi} \exp\left(-b \frac{R_Q}{R_\xi}\right) \quad L = \frac{\hbar R_n}{\pi \Delta}$$

$$R_\xi = R_n \frac{\xi}{w} \quad E_L = (h/2e)^2 / 2L$$



Phase diagram of S-I transition



$$E_s / E_{Li} = (a\lambda^2 / 17.4) \exp(-b / r_\xi) = \alpha_c$$

$$r_\xi = (R^N / R_Q) / (L / \xi)$$

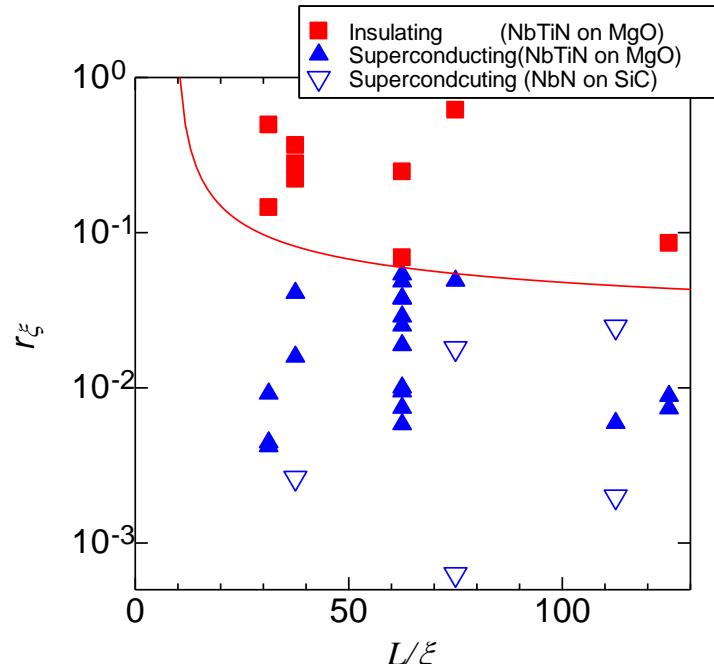
$$r_\xi(\lambda) = b / \ln(a\lambda^2 / 17.4\alpha_c)$$

$$\equiv b / \ln(c\lambda^2 / 17.4)$$

MoGe nanowire $E_s/E_L = 0.3$

NbSi nanowire $E_s/E_L = 0.6$

Mooij et al. New J.Phys 17 (2015) 033006.



**NbN and NbTiN nanowire
 $0.2 < E_s/E_L < 0.5$**



To realize CQPS



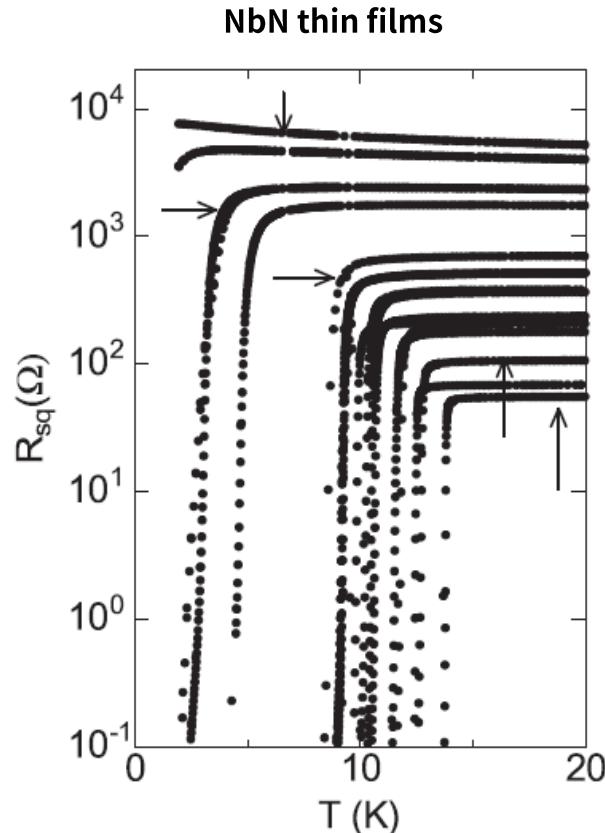
Required property of Material

- High degree of disorder
- homogeneous system
- Oxide or **Nitride**

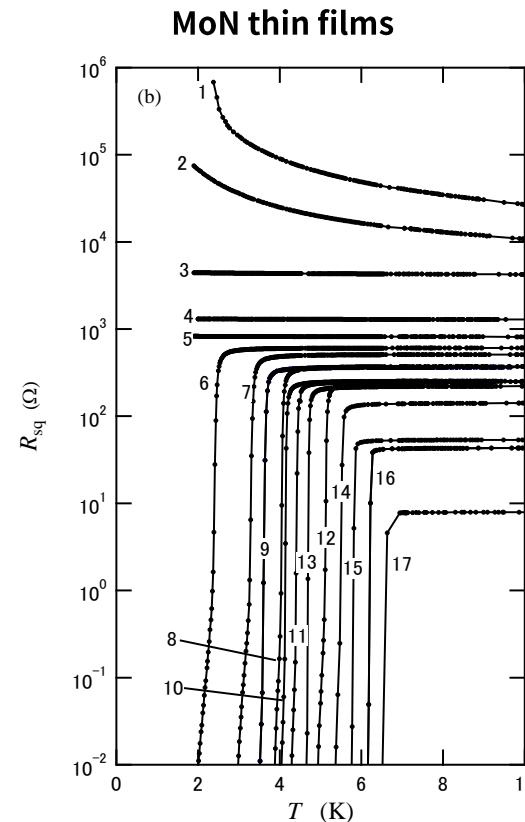
Phase slips energy(Es)

- **Close to SI transition**
- narrow wires

S-I transition for 2D



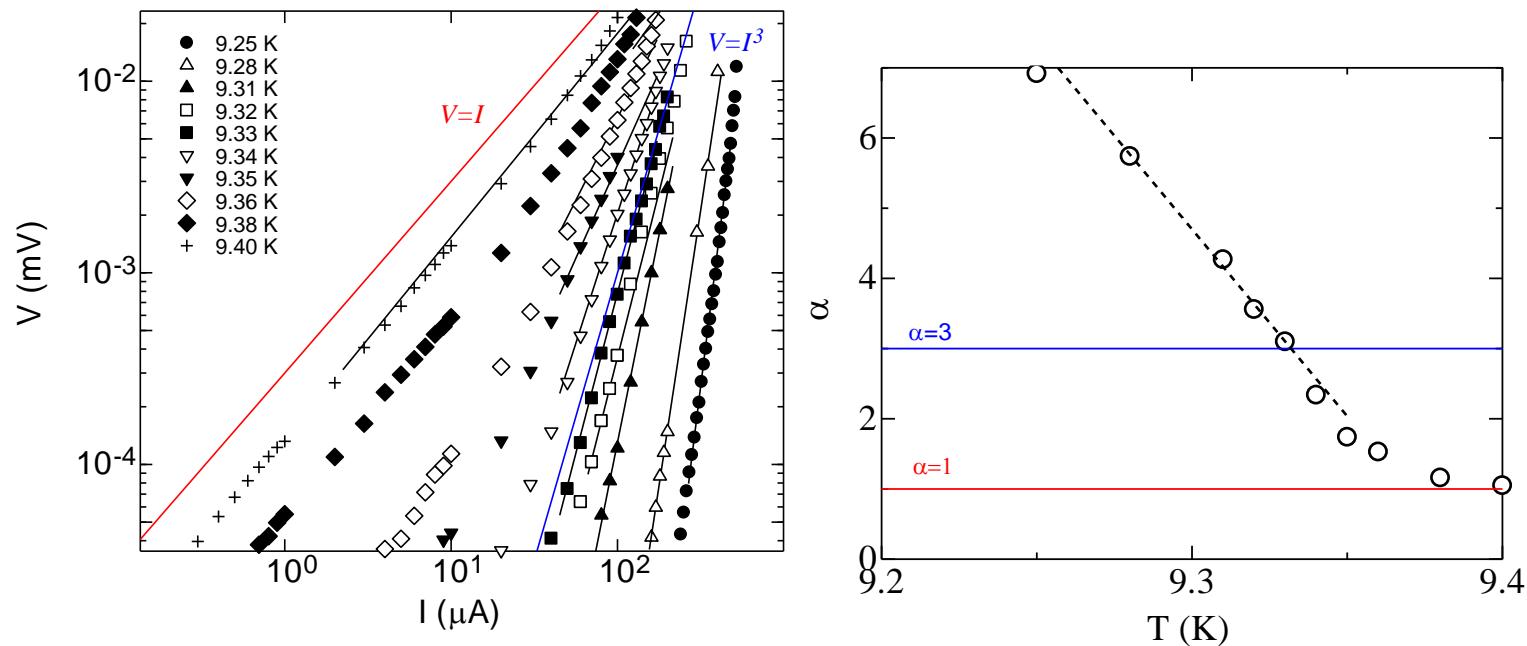
K. Makise et al. Mater. Res. Express
2 (2015) 106001.



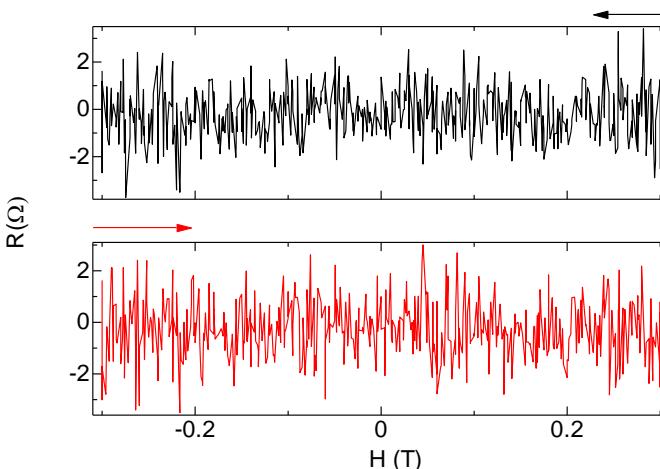
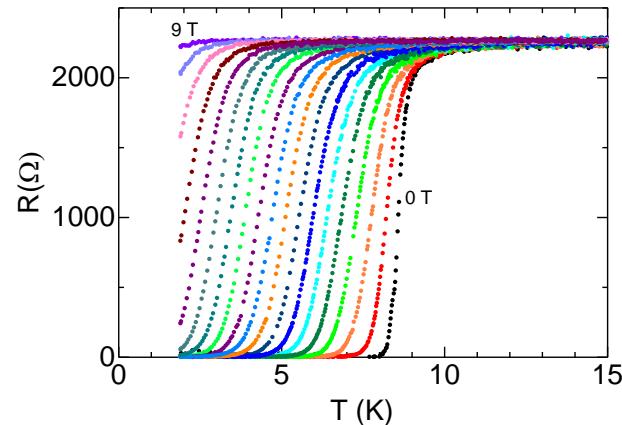
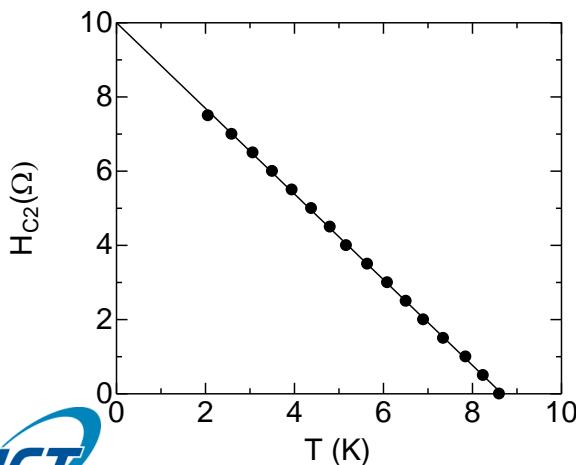
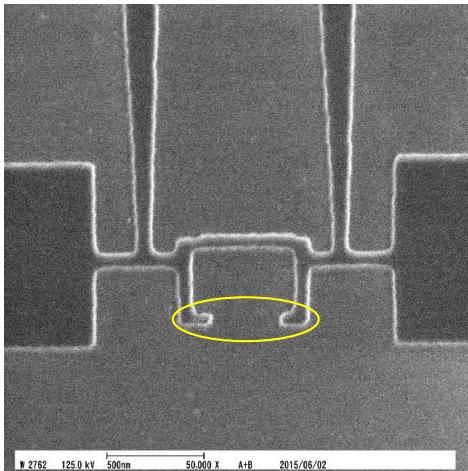
K. Makise et al. J of phys. Cond. Matt.
(2016) Accepted.



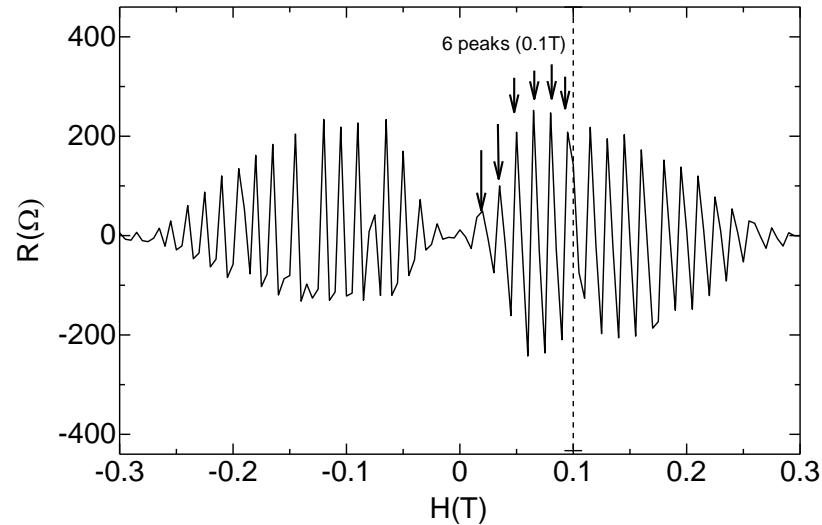
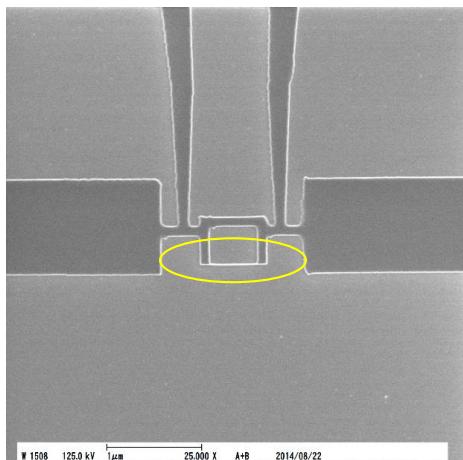
BKT transition (NbTiN films)



Phase slips ring in Mantic field



Phase slips ring in Mantic field



Area of Ring
 $S = 500 \times 250 \text{ nm}^2$

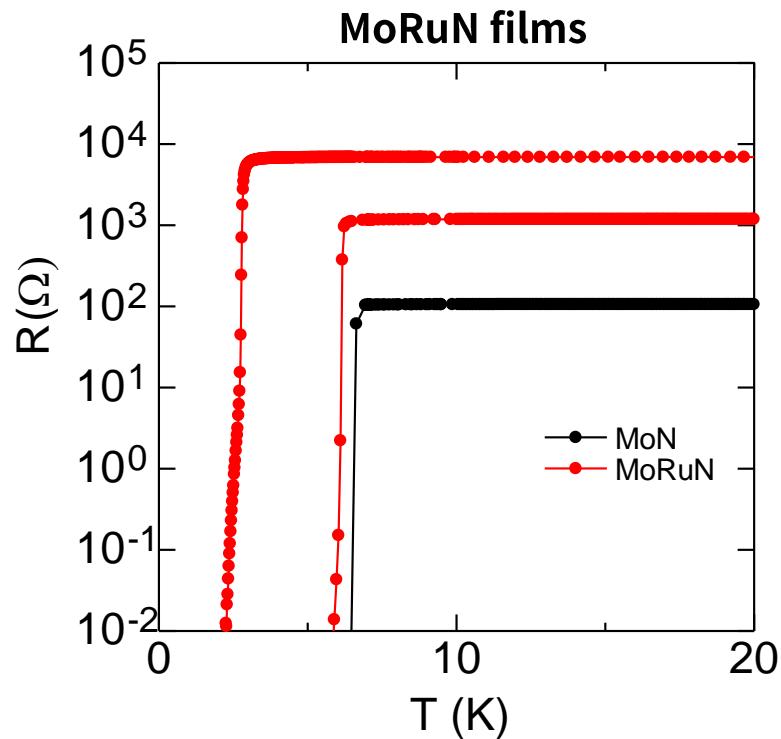
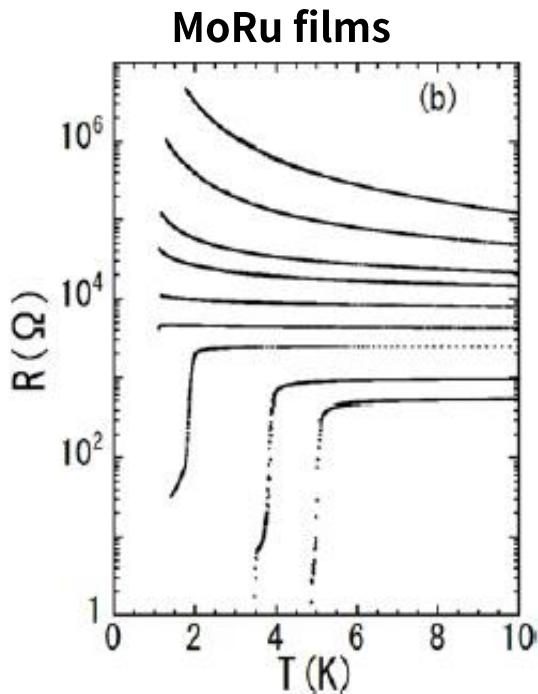
$$\begin{aligned}a_{\square} &= (\Phi_0/B)^{1/2} = (2.07 \times 10^{-15}/0.1)^{1/2} \\&= 143 \text{ nm} \\Vn &= S / (a_{\square} \times a_{\square}) = 6.11 \sim 6\end{aligned}$$

→QPS Qubits



National Institute of Information and Communications Technology

MoRu and MoRuN films

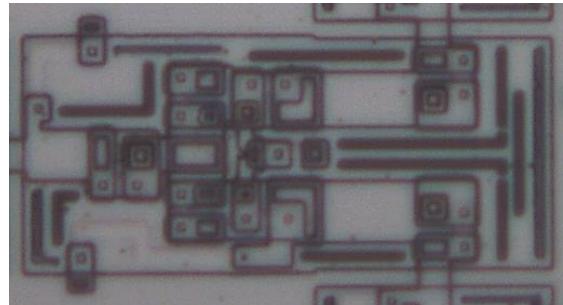


A. Hirakawa, and K. Makise
J. phys. Cond. Matt. 20
(2008)

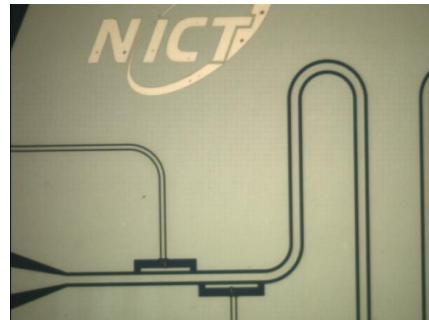
- **High degree of disorder**
- **homogeneous system (amorphous)**
- **Nitride**



Integrated monolithic QPS devices (All Nitride SC)

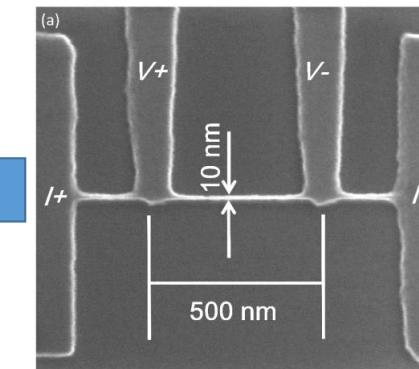


Read out
NbN-SFQ



CPW resonator TIN
MW of Single Photon level
Internal Q above 10^6

QPS NbN, NbTiN, TiN, MoRuN
 \rightarrow CQPS



Summary



- We investigated the transport properties of superconducting NbTiN SNW's in a wide range of RN/L using four-probe method to eliminate the contact resistance.
- The characteristic with resistive tail below T_c for SNWs with high values of E_s/E_L can be well explained by the QPS theory.
- The analysis based on the model for the SNW which is being dual element upto Josephson junction, suggests that the separation of the superconducting and insulator phases may be controlled by the ratio of QPS amplitude energy E_s and inductive energy of SNW E_L, .
- For the present NbTiN series, we observed that SIT may occur at $0.2 < E_s/E_L < 0.5$.